

23 FN
Reg. No.

--	--	--	--	--	--	--	--	--	--	--	--	--	--	--	--	--	--	--	--

Question Paper Code : 66321

M.E. DEGREE EXAMINATION, DECEMBER 2015/JANUARY 2016

First Semester

VLSI Design

VL7102 – VLSI Design Techniques

(Regulations : 2013)

Time : Three Hours

[Maximum : 100 Marks

Answer ALL questions.

PART A – (10 × 2 = 20 Marks)

1. Explain channel length modulation.
2. Define subthreshold slope.
3. Explain lambda based design rules and list its advantages or disadvantages.
4. What is the need to check design rules ?
5. What are the disadvantages of resistive load-nMOSFET logic ?
6. When compared to a resistive load inverter, what are the advantages of an enhancement load inverter ?
7. Explain sheet resistance.
8. What are the important sources of power consumption in a CMOS circuit ?
9. Explain the process of physical design.
10. What is design for test ?

PART – B (5 × 13 = 65 Marks)

11. (a) Consider a p-channel MOSFET with following parameters. The device parameters are as follows :

Oxide thickness 15 nm, channel length 180 nm, channel width 360 nm, carrier mobility $25 \text{ cm}^2\text{V}^{-1}\text{s}^{-1}$, dielectric constant of oxide is $3.9 \epsilon_0$ ($\epsilon_0 = 8.854 \times 10^{-14} \text{ F/cm}$), threshold voltage -0.4 V . The source and bulk of pMOSFET are connected to 1.8 V.

- (i) When gate voltage is 0.2 V, drain voltage is 0.1 V, what is the region of operation of the MOSFET ? Estimate drain current, drain conductance and transconductance.
- (ii) When gate voltage is 1.0 V, drain voltage is 1.5 V, what is the region of operation of the MOSFET ? Estimate drain current, drain conductance and transconductance.

OR

- (b) (i) Explain body bias effect. What is positive body bias effect and negative body bias effect ? What is the effect of body bias on the MOSFET performance and circuit performance ? Is body bias desirable ? What is the best way to control body bias effect ? (8)
- (ii) Threshold voltage of an n-channel MOSFET at zero substrate bias is 0.4 V. The substrate doping of MOSFET is 10^{15} cm^{-3} , oxide thickness is 10 nm. If the substrate is connected to -2 V , what is the change in threshold voltage ? Given that dielectric constant of silicon is $11.8 \epsilon_0$ ($\epsilon_0 = 8.854 \times 10^{-14} \text{ F/cm}$), intrinsic carrier concentration of silicon is $1.5 \times 10^{15} \text{ cm}^{-3}$. (5)

12. (a) (i) Explain various rules associated with stick diagrams. (8)
- (ii) Draw stick diagram of a two input NOR gate. (5)

OR

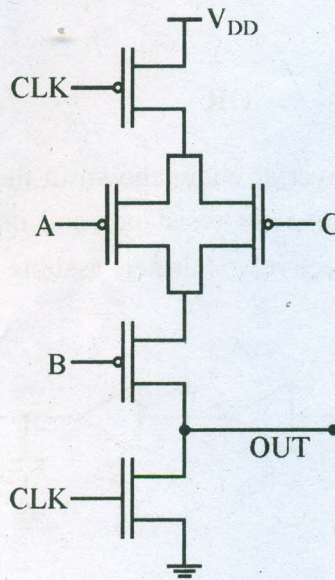
- (b) Explain latch-up in CMOS circuits.

13. (a) Consider a resistive load nMOS inverter in 90 nm technology node has a load resistance of $30 \text{ k}\Omega$. The oxide thickness is 3 nm. Electron mobility is $40 \text{ cm}^2\text{V}^{-1}\text{s}^{-1}$. Width, threshold voltage of nMOSFET are 450 nm and 0.4 V respectively. If the supply voltage is 1.3 V, find noise margins and switching threshold voltage of the inverter. Given that dielectric constant of oxide is $3.9 \epsilon_0$ ($\epsilon_0 = 8.854 \times 10^{-14} \text{ F/cm}$).

OR

- (b) Consider a static CMOS inverter in 90 nm technology node. The oxide thickness is 3 nm. Electron mobility $40 \text{ cm}^2\text{V}^{-1}\text{s}^{-1}$ is twice that of hole mobility. Width of pMOSFET and nMOSFET are 360 nm and 180 nm respectively. Threshold voltage of pMOSFET and nMOSFET are -0.35 V and 0.4 V respectively. If the supply voltage is 1.3 V , find noise margins and switching threshold voltage of the inverter.

14. (a) Consider the logic circuit shown in the figure below.



- (i) Write the Boolean function realized by the circuit and explain working of the circuit. (4)
- (ii) What are the weaknesses of the circuit and explain the methods to overcome the weaknesses. (9)

OR

- (b) Derive equation for raise time and fall time of a static CMOS inverter.

15. (a) Draw transistor level diagram of a NOR-based decoder circuit for two address bits and four word lines and explain its functionality.

OR

- (b) Draw multiple-output domino CMOS representation of a Manchester carry chain.

PART – C (1 × 15 = 15 Marks)

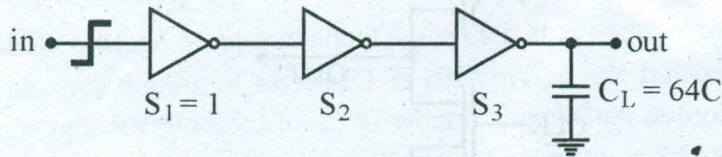
16. (a) Consider function shown in eqn. (1)

$$Y = \overline{A \cdot (B + C) + (D + E) \cdot (F + G)} \quad (1)$$

- (i) Using static CMOS logic, implement function in eqn. (1). Assume that electron mobility is twice that of hole mobility.
- (ii) Using domino-logic style logic, implement function in eqn. (1). Assume that electron mobility is twice that of hole mobility. What is the relative size of both circuits ?

OR

(b) Consider a static CMOS inverter chain shown in the figure below. Each inverter has symmetrical VTC. Equivalent resistance and input capacitance of unit-sized inverter are R and C , respectively. Further, assume that $C_{\text{intrinsic}} = C_{\text{gate}}$ ($\gamma = 1$). Sizing factor $S \geq 1$.



- (i) Find the best sizing factors S_2 and S_3 to minimize propagation delay. (2)
- (ii) What is the minimum delay (in terms of t_{p0}) ? (1)
- (iii) What is the total energy drawn by second stage when the input changes from 0 to 1 (Symbolic answer in C, V) ? (2)
- (iv) What is the energy dissipated as heat by the entire circuit (Symbolic answer in C, V) ? (2)